

What is claimed is:

1. A substrate treating method for performing a predetermined treatment of a plurality of substrates as held by
5 substrate holding device and immersed in a heated treating solution, wherein:

said substrate holding device is heated before
immersing said substrate holding device holding said substrates in the heated treating solution.

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2. A substrate treating method as defined in claim 1,
wherein said substrate holding device is heated by being
placed in a heated atmosphere or heated liquid, before
immersing said substrate holding device holding said substrates in the heated treating solution.

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3. A substrate treating method as defined in claim 2,
wherein said substrate holding device is heated by being
placed in the heated treating solution without holding said
20 substrates, before immersing said substrate holding device holding said substrates in the heated treating solution.

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4. A substrate treating method as defined in claim 2,
wherein said heated liquid is heated pure water.

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5. A substrate treating method as defined in claim 1,
wherein said substrate holding device is heated by heating
device provided therefor, before immersing said substrate
holding device holding said substrates in the heated treating
5 solution.

6. A substrate treating method as defined in claim 1,
wherein said heated treating solution is a phosphoric acid
solution.

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7. A substrate treating method as defined in claim 1,
wherein said heated treating solution is sulfuric acid.

8. A substrate treating method as defined in claim 1,
15 wherein said predetermined treatment of said substrates as
immersed in said heated treating solution is etching treat-
ment.

9. A substrate treating apparatus for performing a
20 predetermined treatment of a plurality of substrates as
immersed in a heated treating solution, comprising:
a treating tank for storing the heated treating solu-
tion;
a substrate transport mechanism for transporting
25 the plurality of substrates;

substrate holding device for holding the substrates received from said substrate transport mechanism and immersing the substrates in the heated the treating solution stored in said treating tank; and

5 control part for keeping said substrate holding device on standby in the heated treating solution stored in said treating tank, before said substrate holding device receives the substrates from said substrate transport mechanism.

10 10. A substrate treating apparatus as defined in claim 9, wherein said heated treating solution is a phosphoric acid solution.

11. A substrate treating apparatus as defined in claim 9,
15 wherein said heated treating solution is sulfuric acid.

12. A substrate treating apparatus as defined in claim 9, wherein said predetermined treatment of said substrates as immersed in said heated treating solution is etching treat-
20 ment.

13. A substrate treating apparatus for performing a predetermined treatment of a plurality of substrates as immersed in a heated treating solution, comprising:
25 a treating tank for storing the heated treating solu-

tion;

a substrate transport mechanism for transporting the plurality of substrates; and

substrate holding device for holding the substrates
5 received from said substrate transport mechanism and
immersing the substrates in the heated the treating solution
stored in said treating tank;

wherein said substrate holding device includes a
plurality of holding rods for holding the plurality of sub-
10 strates in vertical posture, and a back plate supporting said
holding rods in cantilever fashion, said back plate having
heating device.

14. A substrate treating apparatus as defined in claim 13,
15 wherein said heated treating solution is a phosphoric acid
solution.

15. A substrate treating apparatus as defined in claim 13,
wherein said heated treating solution is sulfuric acid.

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16. A substrate treating apparatus as defined in claim 13,
wherein said predetermined treatment of said substrates as
immersed in said heated treating solution is etching treat-
ment.

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